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ABSTRACT of DISCLOSURE

Achemically amplifying type positive resist composition suitable for use in the lithography utilizing an ArF or KrF excimer laser and excellent in the shape of profile is provided, which comprises a resin which has an alkali-soluble group protected by 2-alkyl-2-adamantyl group or 1-adamantyl-1-alkylalkyl group, and which, per se, is insoluble or slightly soluble in alkali but becomes soluble in alkali by the action of an acid; and a sulfonium salt acid generating agent represented by the following formula (I):

$$Q^{1} \xrightarrow{Q^{1}} C \xrightarrow{S^{+}} H_{2}$$

$$Q^{2} \xrightarrow{I} Q^{3} \qquad Q^{4} SO_{3}^{-} \qquad (1)$$

wherein Q^1 , Q^2 and Q^3 independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms; and Q^4 represents perfluoroalkyl which may have a cyclic structure.